





Monte Carlo Particle Device Simulator

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Model	Improvements	Easy, fast
Compact models	Appropriate for Circuit Design	
Driff-Diffusion equations	Good for devices down to 0.5 µm, include µ(E)	
Hydrodynamic Equations	Velocity overshoot effect can be treated property	
Boltzmann Transport Equation Monte Carlo/CA methods	Accurate up to the classical limits	
Quantum Hydrodynamics	Keep all classical hydrodynamic features + quantum corrections	
Quantum Monte Carlo/CA methods	Keep all classical features + quantum corrections	
Quantum-Kinetic Equation (Liouville, Wigner-Boltzmann)	Accurate up to single particle description	
Green's Functions method	Includes correlations in both space and time domain	
Direct solution of the n-body	Can be solved only for small	



- Particle device simulator takes into account the transport of Monte Carlo particles (Super particles).
- Under influence of applied field, determined self-consistently through the solution of decoupled Poisson's and BTE equation over a suitably small time-step.
- The time step is taken typically less than the inverse plasma frequency obtained with the highest carrier density in the device.





Technologies implemented in Monte Carlo Particle Device Simulator:

- > MOSFET
- > FDSOI
- > Tunneling FET
- > MESFET
- > HEMT





- Poisson's solution generated over the node points of the mesh,
- Carrier transport solution is obtained using Ensemble Monte Carlo (EMC) on the full range of space coordinates in accordance with the particle distribution itself.
- Particle-mesh (PM) coupling scheme is used for assignment of carrier charge on different nodes and for calculation force on each charges.





- The classification of Particle-mesh (PM) coupling scheme is included as;
 - Carrier charge assign at mesh nodes Charge in Cloud (CIC) scheme,
 - Solution of Poisson's equation on node points through Successive over Relaxation (SOR) method,
 - Calculation of the mesh defined electric field components,
 - Interpolation of forces at the particle positions.





- Particle Device Simulator (PDS) contains consistent boundary conditions with those imposed on the potential on the field.
- The particle boundary conditions contain Neumann (zero electric field in the direction normal to the surface) and Dirichlet (contacts) conditions.
- At Neumann boundary the reflecting boundaries has been taken.





- Density-gradient model: implemented dependent on non-local quantities.
- Density gradient model is first-order quantum-correction model describe carrier confinement by locally modifying the electrostatic potential through a correction potential γ.
- The Boltzmann-Wigner transport equation can be derived as

$$\frac{\partial f}{\partial t} + v \cdot \nabla_{\mathbf{r}} \mathbf{f} - \frac{\mathbf{q}}{\hbar} \sum_{\alpha=0}^{\infty} \frac{(-1)^{2\alpha}}{4^{\alpha}(2\mathbf{n}+1)!} \nabla_{k}^{2n+1} V(\mathbf{r}) \cdot \nabla_{k}^{2n+1} f = \left(\frac{\partial f}{\partial t}\right)_{coll}$$





• The corrected quantum effect is included as

$$\frac{\partial f}{\partial t} + \frac{\hbar k}{m^*} \nabla_{\mathbf{r}} \mathbf{f} - \frac{1}{\hbar} \nabla_{\mathbf{r}} \left(V(\mathbf{r}) - \nabla_{\mathbf{r}}^2 \mathbf{\emptyset} \right) \nabla_{\mathbf{k}} f = \left(\frac{\partial f}{\partial t} \right)_{coll}$$

The correction potential term in multidimensional space is

$$\gamma(\mathbf{r},t) = \frac{\hbar^2}{12\lambda k_b T m^*} \left(\nabla_{\mathbf{r}}^2 \emptyset(\mathbf{r},t) - \frac{1}{2k_b T} (\nabla_{\mathbf{r}} \emptyset(\mathbf{r},t))^2 \right)$$

The fitting parameter λ is determined by comparing the carrier density in a device structure to the carrier density obtained by the solution of Poisson Equation.

PARTICLE MESH COUPLING



- The particle-mesh method is a widespread model for space charge calculations.
- Particle dynamics under applied electric field requires accurate solution of Poisson's equation.
- The particle simulation means the assignation of the particle's charge to the rectangular mesh.
- Two types of the most famous schemes:
 - ➢Nearest Grid Point (NGP)
 - ➢Cloud In Cell (CIC)





FLOW CHART





Single Gate Double Gate Leff (nm) 22 14 10 22 14 10 Weff (nm) 10 8 10 8 0.25 0.2	
$\begin{array}{ c c c c c c c c c c c c c c c c c c c$	
Weff(nm) 10 8 10 8 Training 1 0.95 0.75 0.75 0.75 0.75	
$\overline{0}$ $10x(nm)$ 1 0.85 0.75 0.75 0.85 0.75	5
Doping (/cm ³) 1×10^{24} 5×10^{24} 2×10^{25} 2×10^{25} 5×10^{24} 2×10^{25}	25
Tsol (nm) 40 30 20 20 30 20	
Set Vth (mV) 0.3 0.22 0.2 0.2 0.4 0.5	
SS (/mV/dec) 63.3 67.9 82.9 82.9 87.4 72.2	2
gm (mS/µm) 0.252 0.437 0.499 0.499 0.494 0.44	9

FDSOI TECHNOLOGY UP TO 7NM



- > Intervalley,
- Acoustic and
- Coulomb









a) 14nm FDSOI MOSFET b) 10nm FDSOI MOSFET c) 7nm FDSOI MOSFET



Transfer I_d - V_g Characteristics

Drain Voltage=0.6V

0.2 0.3 0.4 0.5 0.6



+ 7nm FDSOI

10nm FDSOI

14nm FDSOI

1.05 1.00

0.95

0.90

0.85

0,80

0.75 0.70

0.65

0.60

(un/vn)pI 0.35

0.30

0,25 0.20

0.15

0.10

0,05

0,00

-0.05 -0.10

-0.15

-0,3

-0,4

-0.1

-0.2

X













I_V_Characteristic







Thank You Contact us



